

ELT 223 : Lithography for Nanofabrication

This course is a hands-on treatment of all aspects of advanced pattern transfer and pattern transfer equipment including probe techniques; stamping and embossing; e-beam; and optical contact and stepper systems. The course is divided into five major sections. The first section is an overview of all pattern generation processes covering aspects from substrate preparation to tool operation. The second section concentrates on photolithography and examines such topics as mask template, and mold generation. Chemical makeup of resists will be discussed including polymers, solvents, sensitizers, and additives. The role of dyes and antireflective coatings will be discussed. In addition, critical dimension (CD) control and profile control of resists will be investigated. The third section will discuss the particle beam lithographic techniques such as e-beam lithography. The fourth section covers probe pattern generation and the fifth section explores embossing lithography, step-and-flash, stamp lithography, and self-assembled lithography.

Credits 3

Notes

Course offered on the Penn State University Campus in partnership with the Penn State University Nanotechnology Program.